THIN-FILM MATERIALS

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Certificate of Analysis (CoA)

Dec. 2, 2025

Product Name: Aluminum Oxide Sputtering Target
Chemical Formula: Al_2O_3
Purity: 99.99% (4N)
Dimensions: Ø50.8 mm (2”) × 2.0 mm (±0.1 mm)
Backing Plate: Elastomer-bonded to 1.0 mm OFHC Copper plate
Quantity: 1 pc
Lot Number: CSJM-251202TB
Manufactured by: Thin-Film Materials

Physical Description

- Form: Ceramic sputtering target
- Appearance: White, dense, fine-grained ceramic
- Crystal Structure: α-Al_2O_3 (Corundum)
- Theoretical Density: 3.98 g/cm³
- Fabrication: High-temperature sintering and precision machining

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Chemical Composition (by XRF / ICP-OES)

Element	**Symbol**	**Max. Content (ppm)**
Aluminum	Al	Balance (>99.99%)
Silicon	Si	<20
Iron	Fe	<20
Calcium	Ca	<20
Magnesium	Mg	<20
Sodium	Na	<10
Nickel	Ni	<10
Copper	Cu	<10
Other elements (each)	–	<10
Total Impurities	–	<100 ppm

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Handling & Storage

- Store in vacuum-sealed packaging.
- Avoid moisture and rapid temperature changes.
- Handle with clean gloves to prevent contamination.

Declaration

This product has been manufactured and tested according to our quality control standards and meets the specifications stated herein.

Authorized Signature:

Inspection Certificate by: **Nancy Liu**

Approver by: **Chen Qiang**

chen Qiang